

Title (en)

METHOD FOR REMOVING RESIDUAL MONOMERS FROM POLYOXYMETHYLENES

Title (de)

VERFAHREN ZUR ENTFERNUNG VON RESTMONOMEREN AUS POLYOXYMETHYLENEN

Title (fr)

PROCEDE POUR ELIMINER DES MONOMERES RESIDUELS DE POLYOXYMETHYLENES

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Application

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Abstract (en)

[origin: WO2005113623A1] The invention relates to a method for removing residual monomers from polyoxymethylene homo- or copolymers with the following method steps: a) in a degasifying device, the residual monomers are drawn out in the form of vapors from the polymers; b) the residual monomer vapors are led away via a vapor line; c) in a condensation device, the residual monomers are condensed out of the vapors at 1.09 to 102.4 bar and at 102 to 230 DEG C, during which a temperature of at least 102 DEG C must be maintained at every point on the condensation device, and the surfaces of the condensation device that come into contact with the vapors are covered with a liquid film comprised of condensed residual monomers.

IPC 8 full level

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